			DB	Time stamp
L Number	Hits	Search Text	USPAT;	2003/04/02 15:57
1	27606	((low near10 dielectric) (organo near3	US-PGPUB	
	1000	silic\$5 near3 glass)) (((low near10 dielectric) (organo near3	USPAT;	2003/04/02 15:51
2	1300	silic\$5 near3 glass))) and (plasma near10	US-PGPUB	
		(treat\$6))		
_	05.20	(((low near10 dielectric) (organo near3	USPAT;	2003/04/02 15:52
3	2539	silic\$5 near3 glass))) and (reduc\$3 near5	US-PGPUB	
		Silicso Hears glass/// and (reduces mours		
		<pre>(agent gas plasma)) ((((low near10 dielectric) (organo near3</pre>	USPAT;	2003/04/02 15:20
4	3454	silic\$5 near3 glass))) and (plasma near10	US-PGPUB	
		(treat\$6))) ((((low near10 dielectric)	05 10105	
		(organo near3 silic\$5 near3 glass))) and		
		(organo nears silicas nears grass))		
		<pre>(reduc\$3 near5 (agent gas plasma))) (((((low near10 dielectric) (organo near3</pre>	USPAT;	2003/04/02 15:58
5	2106	(((((low nearly dielectric) (organo hears	US-PGPUB	
		silic\$5 near3 glass))) and (plasma near10	05 10105	
		(treat\$6))) ((((low near10 dielectric) (organo near3 silic\$5 near3 glass))) and		ļ
		(organo near3 silicas near3 glass))) and		
		(reduc\$3 near5 (agent gas plasma)))) and		
		(hydrogen "H.sub.2" and (argon Ar nitrogen		ĺ
		"N. sub.2"))	USPAT;	2003/04/02 15:23
6	1848	((((((low near10 dielectric) (organo near3	US-PGPUB	2000,01,02
	1	silic\$5 near3 glass))) and (plasma near10	05-16100	
		(treat\$6))) ((((low near10 dielectric)		
		(organo near3 silic\$5 near3 glass))) and		
		(reduc\$3 near5 (agent gas plasma)))) and		
		(hydrogen "H.sub.2" and (argon Ar nitrogen		
		"N.sub.2"))) and (via trench hole open\$4)	USPAT;	2003/04/02 15:53
7	361	(((((((low near10 dielectric) (organo	US-PGPUB	2003/04/02 13:00
		near3 silic\$5 near3 glass))) and (plasma	03-FGF0D	
		near10 (treat\$6))) ((((low near10		
		dielectric) (organo near3 silic\$5 near3		1
		glass))) and (reduc\$3 near5 (agent gas		i
		plasma)))) and (hydrogen "H.sub.2" and		1
		(argon Ar nitrogen "N.sub.2"))) and (via		
		trench hole open\$4)) and (wet near8		
		(treat\$3 etch\$3 clean\$3))	USPAT;	2003/04/02 15:55
8	206	(((((((low near10 dielectric) (organo	US-PGPUB	2003/04/02 13:33
		near3 silic\$5 near3 glass))) and (plasma	US-PGPUB	
		near10 (treat\$6))) ((((low near10		
		dielectric) (organo near3 silic\$5 near3		
		glass))) and (reduc\$3 near5 (agent gas		
		plasma)))) and (hydrogen "H.sub.2" and		
		(argon Ar nitrogen "N.sub.2"))) and (via		
		trench hole open\$4)) and (wet near8		
	}	(treat\$3 etch\$3 clean\$3))) and (HF		
		(hydrogen near3 fluoride) (hydro near3	1	
		fluoric near3 acid) (sulfuric near3 acid) ("H.sub.2" adj "SO.sub4") ((citric acetic	1	
		("H.Sub.z" adj "SU.Sub4 / ((Citit acetic		
1	17020	oxallic) near5 acid)) ((low near10 dielectric) (organo near3	EPO; JPO;	2003/04/02 15:51
9	17236	((low near10 dielectric) (organo hear3 silic\$5 near3 glass))	DERWENT;	
		SILICOD Heard Grass))	IBM TDB	
10	100	(((low near10 dielectric) (organo near3	EPO; JPO;	2003/04/02 15:52
10	123	(((low hear10 dielectric) (organo hear3 silic\$5 near3 glass))) and (plasma near10	DERWENT;	
			IBM TDB	
, ,	1	(treat\$6)) (((low near10 dielectric) (organo near3	EPO; JPO;	2003/04/02 15:52
11	123	(((low nearly dielectric) (organo hears	DERWENT;	2003, 01, 02 10.02
		silic\$5 near3 glass))) and (reduc\$3 near5	IBM TDB	
1		(agent gas plasma))	EPO; JPO;	2003/04/02 15:52
12	235	((((low near10 dielectric) (organo near3		2003/04/02 13:32
		silic\$5 near3 glass))) and (plasma near10	DERWENT;	
		(treat\$6))) ((((low near10 dielectric)	IBM_TDB	
		(organo near3 silic\$5 near3 glass))) and		
1		(reduc\$3 near5 (agent gas plasma)))	EPO; JPO;	2003/04/02 15:52
13	34	(((((low near10 dielectric) (organo near3	DERWENT;	2003,04,02 13.32
		silic\$5 near3 glass))) and (plasma near10		1
		(treat\$6))) ((((low near10 dielectric)	IBM_TDB	
	1	(organo near3 silic\$5 near3 glass))) and		
		(reduc\$3 near5 (agent gas plasma)))) and		1
		(hydrogen "H.sub.2" and (argon Ar nitrogen	1	
1	1	"N.sub.2"))	<u> </u>	<u></u>

Search History 4/2/03 4:36:10 PM Page 1

14	2	((((((low near10 dielectric) (organo near3	EPO; JPO;	2003/04/02 15:53
1 1		silic\$5 near3 glass))) and (plasma near10	DERWENT;	
	1	(treat\$6))) ((((low near10 dielectric)	IBM_TDB	
		(organo near3 silic\$5 near3 glass))) and		
		(reduc\$3 near5 (agent gas plasma)))) and		
1		(hydrogen "H.sub.2" and (argon Ar nitrogen		
		"N.sub.2"))) and (wet near8 (treat\$3		
Ì		<pre>etch\$3 clean\$3)) (((((low near10 dielectric) (organo near3</pre>	EPO; JPO;	2003/04/02 15:58
15	2	silic\$5 near3 glass))) and (plasma near10	DERWENT;	
		(treat\$6))) ((((low near10 dielectric)	IBM TDB	
		(organo near3 silic\$5 near3 glass))) and	_	
		(reduc\$3 near5 (agent gas plasma)))) and		. 1
		(hydrogen "H.sub.2" and (argon Ar nitrogen	1	
		"N.sub.2"))) and (HF (hydrogen near3		
		fluoride) (hydro near3 fluoric near3 acid)		
		(sulfuric near3 acid) ("H.sub.2" adj		
		"SO.sub4") ((citric acetic oxallic) near5		
		acid))	USPAT;	2003/04/02 15:57
16	4772	(damascene (dual near3 damascene))	US-PGPUB	2003, 01, 02 2010
	779	((damascene (dual near3 damascene))) and	USPAT;	2003/04/02 15:58
17	119	(((low near10 dielectric) (organo near3	US-PGPUB	
		silic\$5 near3 glass)) same plasma)		
18	543		USPAT;	2003/04/02 15:58
10		(((low near10 dielectric) (organo near3	US-PGPUB	
		silic\$5 near3 glass)) same plasma)) and		
		(hydrogen "H.sub.2" and (argon Ar nitrogen		
		"N.sub.2"))		2003/04/02 15:59
19	162	((((damascene (dual near3 damascene))) and	USPAT; US-PGPUB	2003/04/02 13:39
		(((low near10 dielectric) (organo near3	US-PGPUB	
		silic\$5 near3 glass)) same plasma)) and		1
		(hydrogen "H.sub.2" and (argon Ar nitrogen "N.sub.2"))) and (HF (hydrogen near3		
		fluoride) (hydro near3 fluoric near3 acid)		
		(sulfuric near3 acid) ("H.sub.2" adj		
		"SO.sub4") ((citric acetic oxallic) near5		
		acid))		

Page 2